

The below additional citation is in reference to the Plasma Hardened Photoresist (PHPR) Process utilized in the above Report (Pages 86-89), regarding the Potassium and Sodium Sensing ISFET Device and Array:

M. Zhou, D. Zhang, D. Zhang, H. Sun, Z. Liu, T. Chen, C.-H. Liu, X. Wang, Z. Zhong, and Y. Shi, "Photoresist as a choice of molecularly thin gate dielectrics in graphene-based devices," *AIP Publishing*, 01-Mar-2021. [Online]. Available: <https://aip.scitation.org/doi/10.1063/5.0034996>. [Accessed: 12-Aug-2022].